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Sheet	1	of	2
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Application Number	10/579,511
Filing Date	30 May 2007
First Named Inventor	Torbojrn Sandstrom
Art Unit	1756
Examiner Name	Unassigned
Attorney Docket Number	MLSE 1060-1

[illegible]

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages Or Relevant Figures Appear	T ⁶
		Country Code ³ -Number ⁴ -Kind Code ⁵ (if known)				
	B1	JP 02135723 A2	05-24-1990	Nikon Corp.	Abstract only	
	B2	JP 03179357 A2	08-05-1991	Nikon Corp.	Abstract only	
	B3	WO 0193303 A2	12-06-2001	Chabala et al.		
	B4	WO 03079111 A1	09-25-2003	Tyrell et al.		
	B5	EP 1324137 A2	07-02-2003	ASML Netherlands B.V.		

Examiner Signature	/Brittany Raymond/	Date Considered	09/28/2010
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(Use as many sheets as necessary)</i>				Complete if Known	
				Application Number	10/579,511
				Filing Date	30 March 2007
				First Named Inventor	Torbjorn Sandstrom
				Art Unit	1756
				Examiner Name	Unassigned
Sheet	2	of	2	Attorney Docket Number	MLSE 1060-1

NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	C1	PCT International Search Report and Written Opinion of the International Searching Authority for International Application No. PCT/SE2004/001701 (filed 19 November 2004), mailed 11 March 2005.	
	C2	PCT International Search Report for International Application No. PCT/SE2004/001700 (filed 19 November 2004), mailed 02 May 2005.	
	C3	MCCARTHY, A. M. et al. "A Novel Technique for Detecting Lithographic Defects," IEEE Transactions on Semiconductor Manufacturing, Vol.1, No. 1 p.10-15 (Feb. 1998).	
	C4	NEWMAN, T. et al. "Evaluation of OPC Mask Printing with a Raster Scan Pattern Generator," Proceedings of SPIE, Vol. 4691, Optical Microlithography XV, p.1320-1330 (July 2002).	
	C5	Rieger, M. L. et al. "Lithographic Alternatives to PSM Repair," Proceedings of SPIE, Vol. 1674, Optical/Laser Microlithography V, p.609-617 (1992).	
	C6	Rieger, M. L. et al. "Image Quality Enhancements for Raster Scan Lithography," Proceedings of SPIE, Vol. 922, Optical/Laser Microlithography, p. 55-64 (March 1988).	
	C7	Stephanakis, A. C. et al. "Advances in 1 : 1 Optical Lithography," Proceedings of SPIE, Optical Microlithography VI, Vol. 772, p.74-85 (1987).	
	C8	WOLF, S. "Advanced Lithography," p.493-513 in Silicon Processing for the VLSI Era, Vol.1 - Process Technology, Lattice Press, Inc. (1986).	

Examiner Signature	/Brittany Raymond/	Date Considered	09/28/2010
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Applicant's unique citation designation number (optional). ² Applicant is to place a check mark here if English language Translation is attached.

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